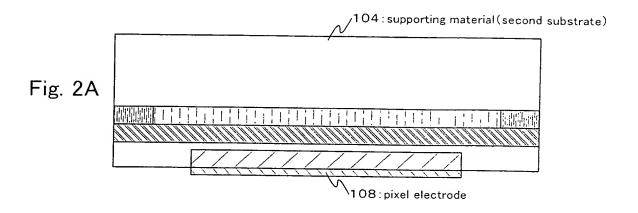
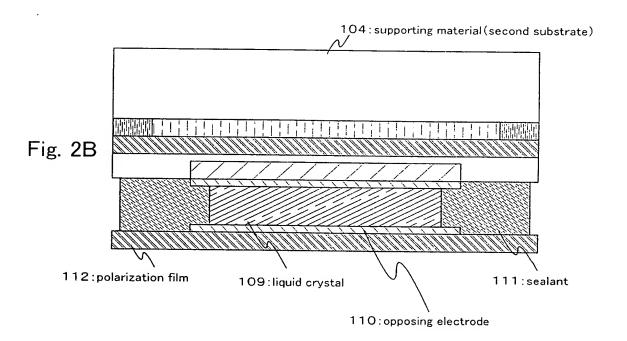


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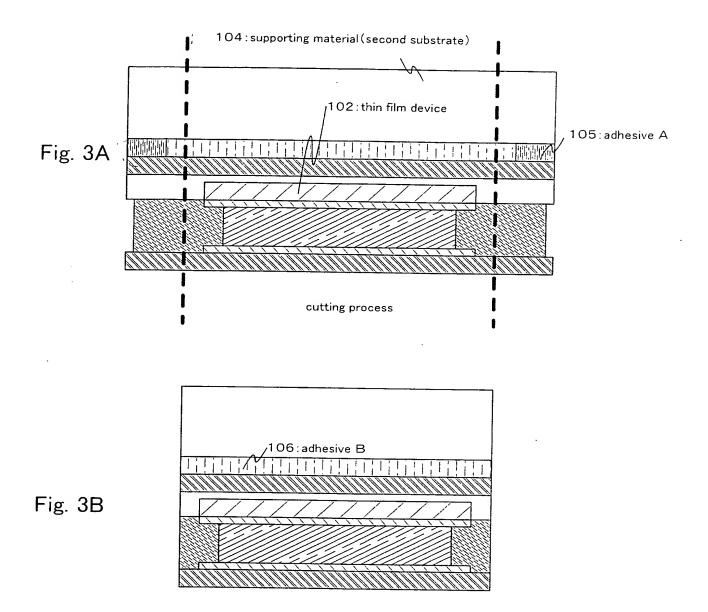
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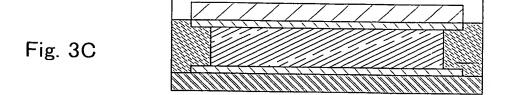
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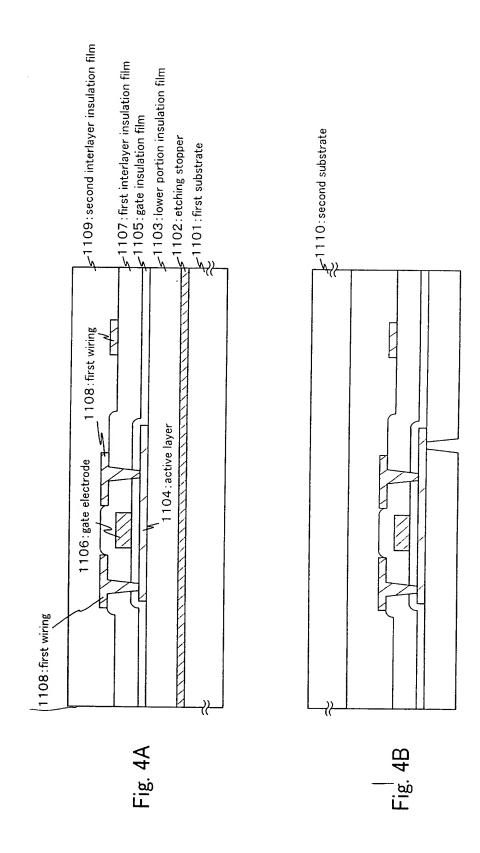
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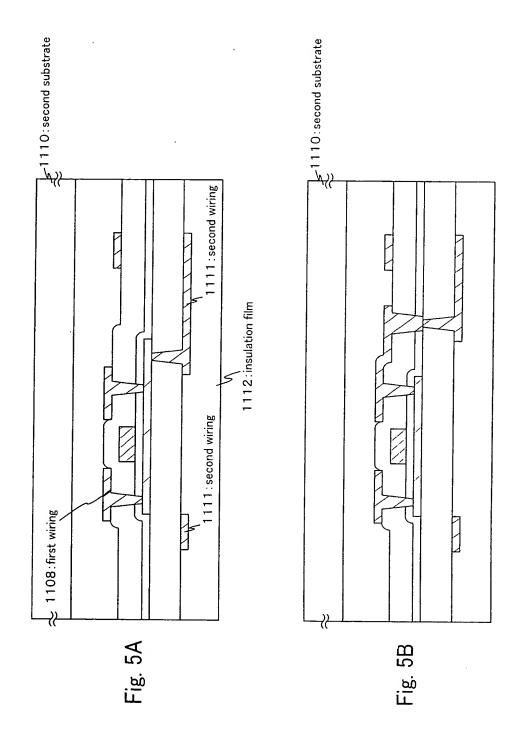
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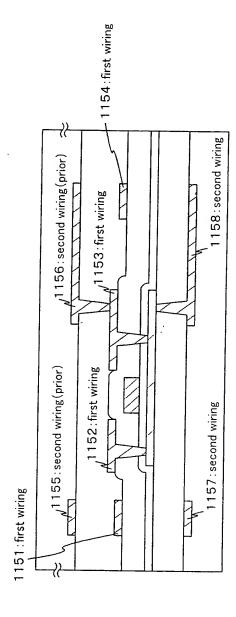
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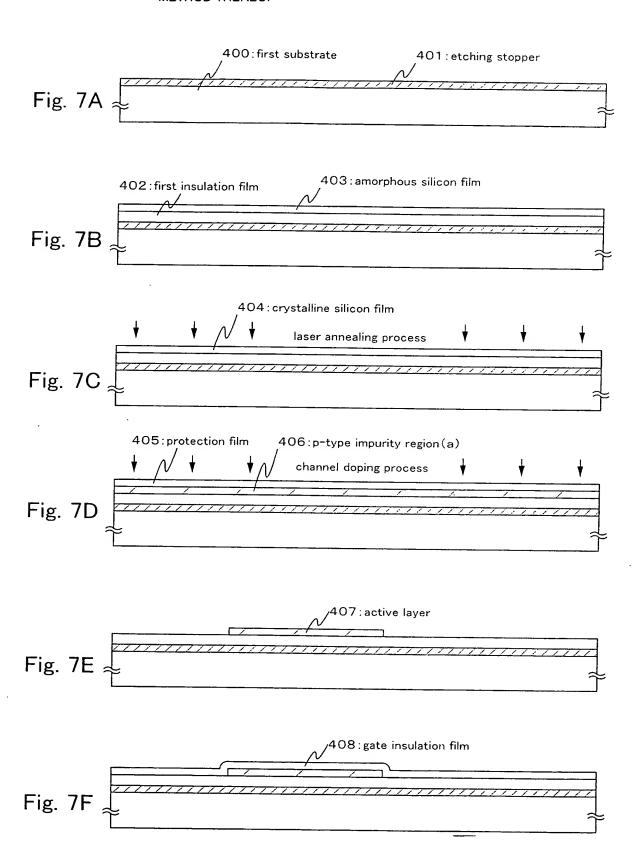
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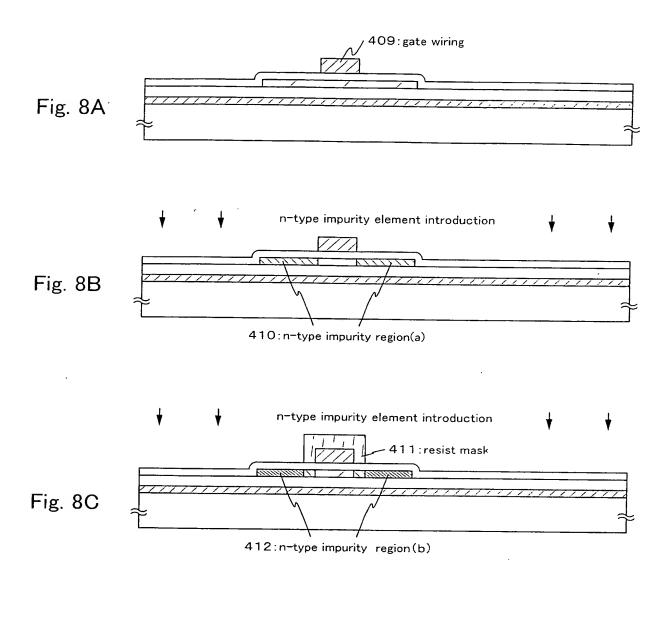


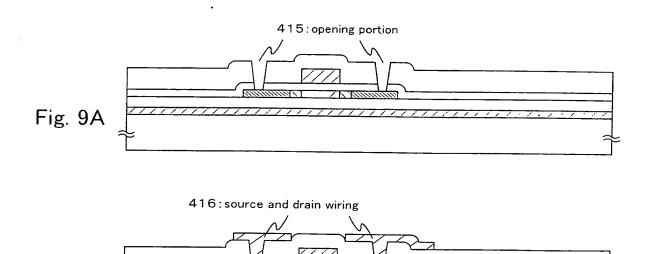
Fig. 8D

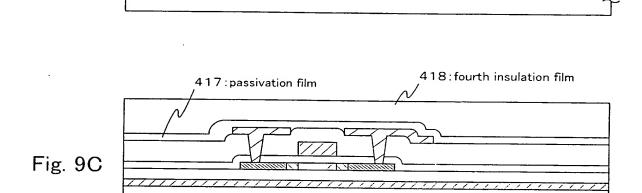
414: third insulation film

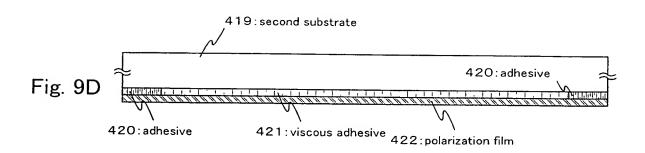
414: third insulation film

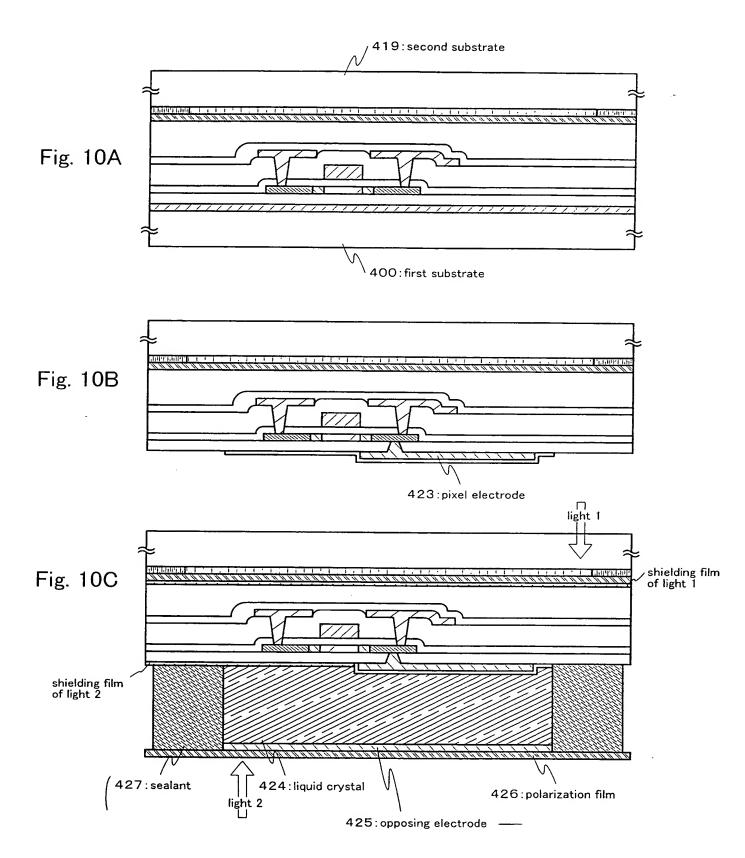
413: channel region

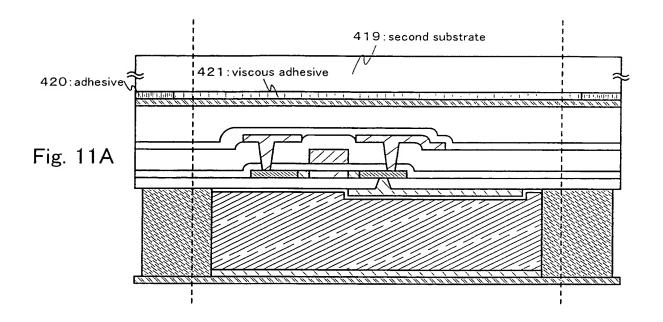
Fig. 9B



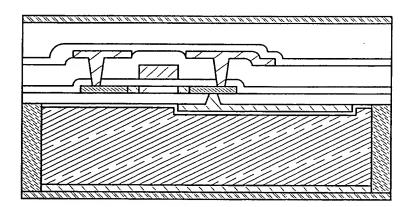












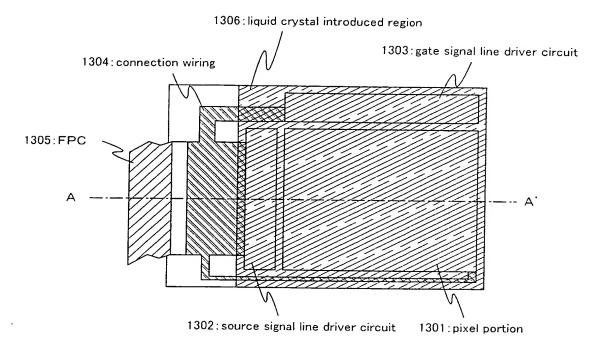


Fig. 12

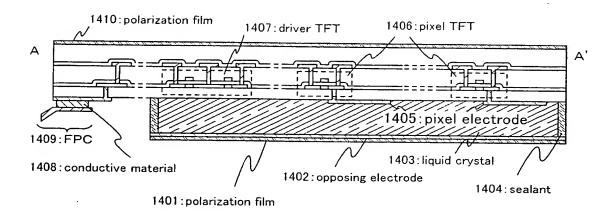
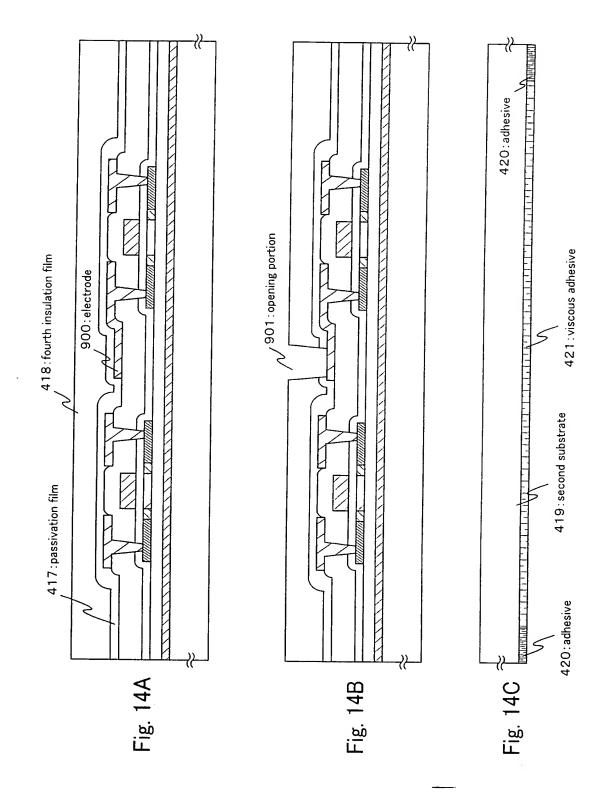
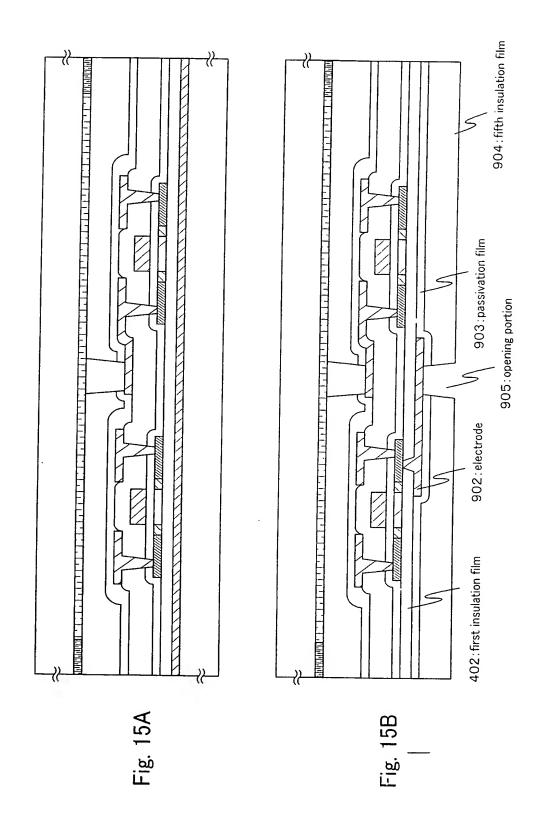


Fig. 13



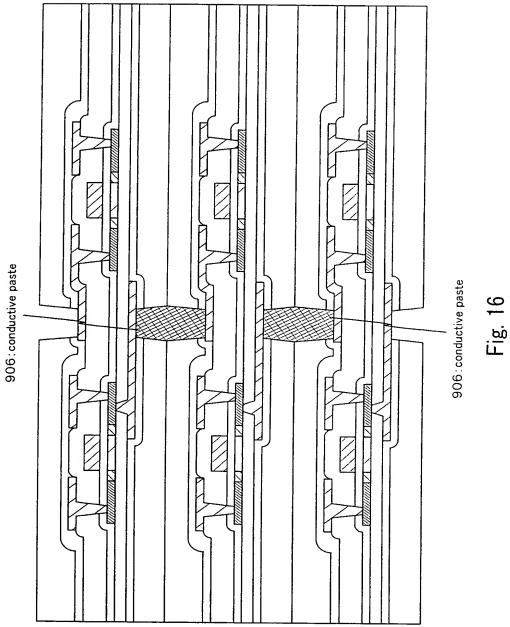
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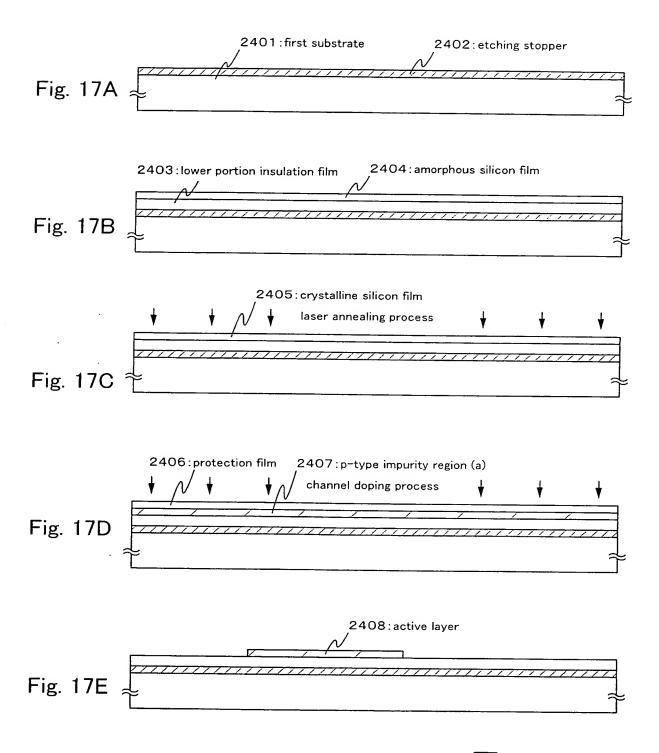
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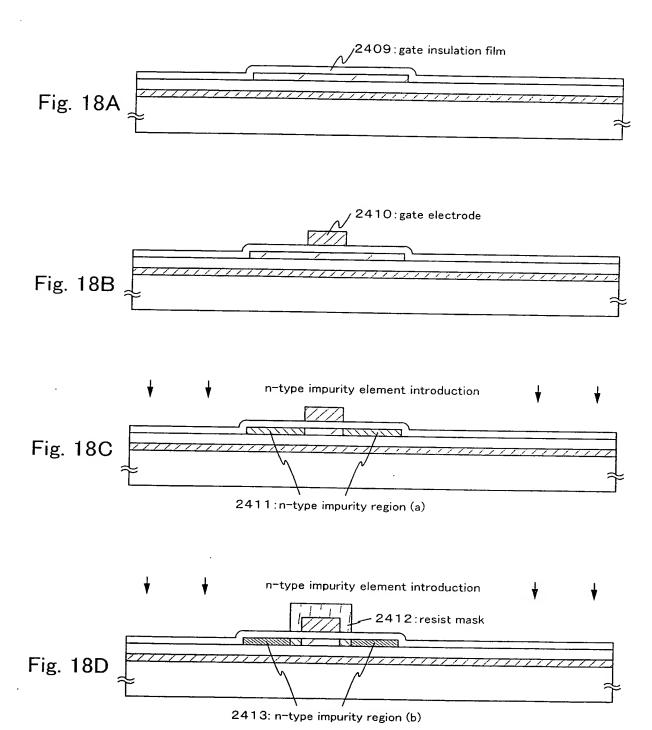
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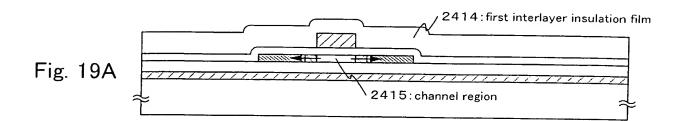
Applicant(s): Akira Ishikawa SEMICONDUCTOR DEVICE AND MANUFACTURING

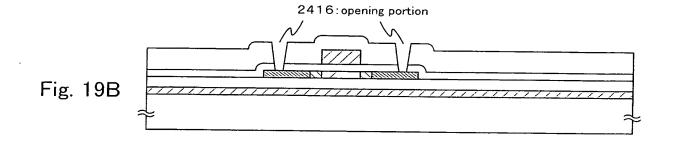


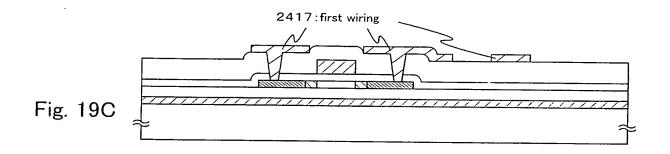
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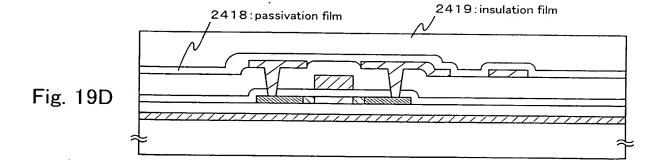
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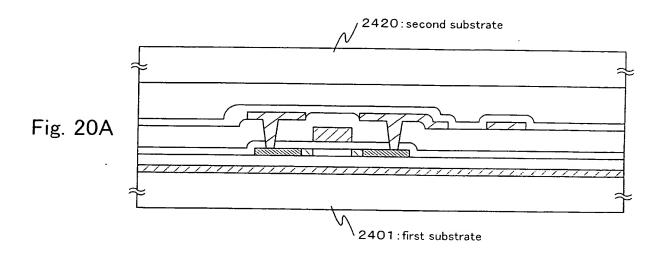


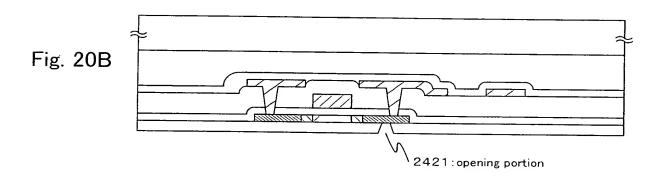


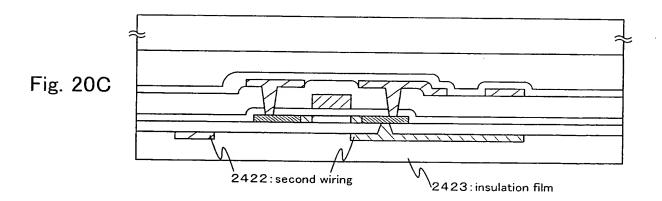




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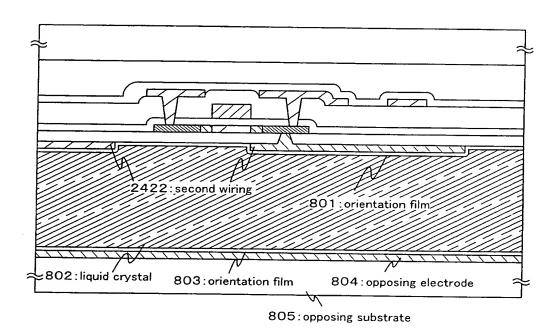


Fig. 21

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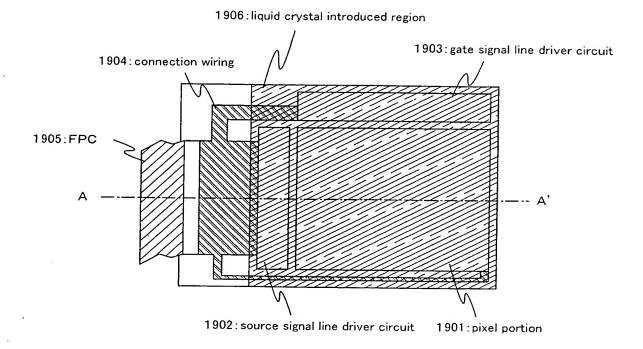


Fig. 22

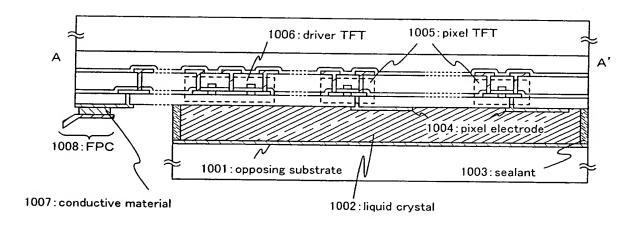
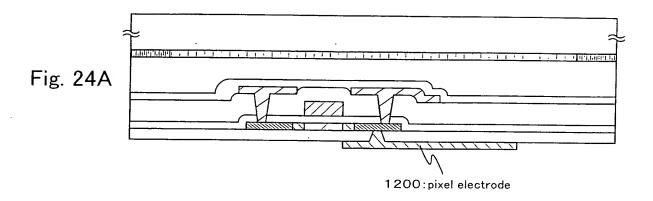
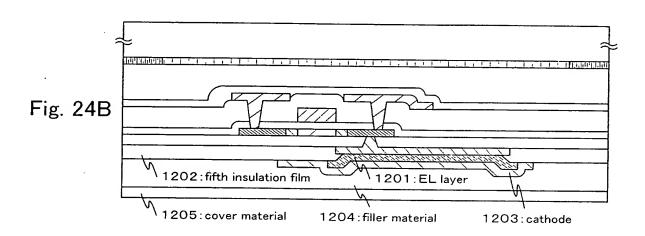
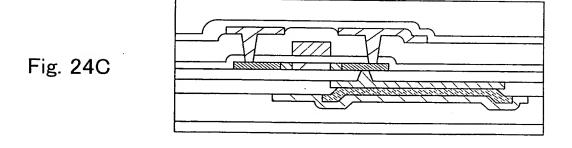


Fig. 23

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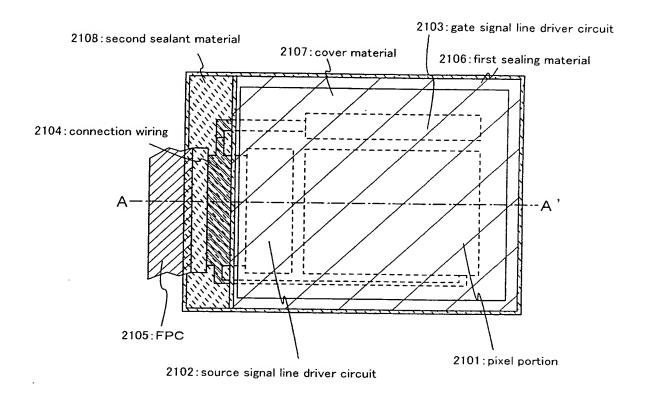


Fig. 25

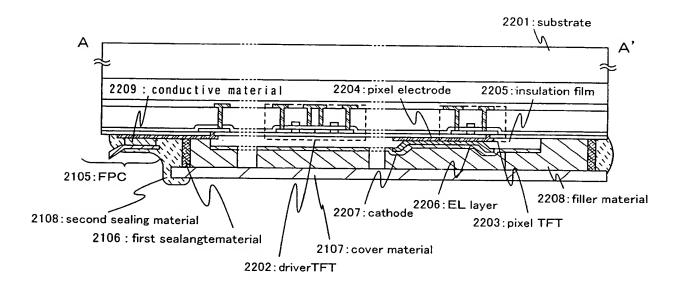


Fig. 26 —

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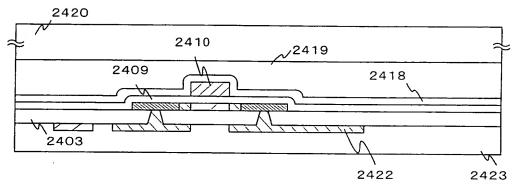


Fig. 27

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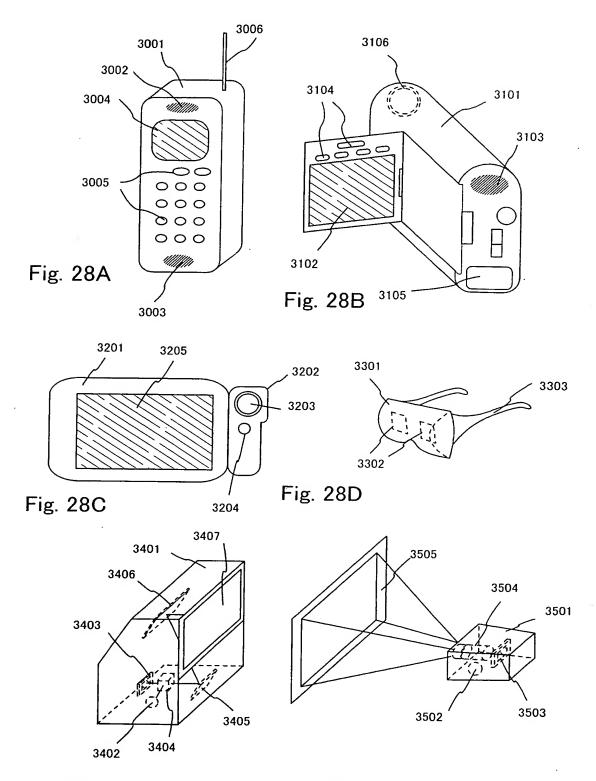


Fig. 28E

Fig. 28F